

ABSTRACT OF THE DISCLOSURE

The present invention provides a process apparatus including an airtight process vessel, an exhaust system for exhausting gas from the process vessel, and a  
5 baffle plate for partitioning the process vessel into a process chamber for processing an object and an exhaust passage communicating with the exhaust system, the baffle plate has a plurality of slits through which the process chamber and the exhaust passage communicate  
10 with each other, and each of the slits has a tapered surface on an inner surface toward the process chamber, the tapered surface corresponding to not less than 1/4 of a depth of the slit.